

# Spectroscopy to Support Short Wavelength Light Source Development

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# Outline

- Applications of Laser Produced Plasmas (LPPs) as Light Sources for Lithography and Microscopy.
- Properties of LPPs
- Properties of  $\Delta n = 0$  UTAs
- Application of  $\Delta n = 1$  UTAs
- Conclusions/Outlook

# Lithography and Moore's Law



Number of transistors doubles approximately every 18 months

Predicated on decrease in feature size

#### The Twilight of Moore's Law: Economics

Altic Comiconductor	1				
Altis Semiconductor	Donghu Uitok	Т			
Dongou Hitek	Dongou Hitek				
Freescale	Freescale				
Fujitsu	Fujitsu		1		
Globalfoundries	Globalfoundries	Freescale	1		
Grace Semiconductor	Grace Semiconductor	Fujitsu	1		
IBM	IBM	Globalfoundries	1		
Infineon	Infineon	IBM		-	
Intel	Intel	Infineon	Fujitsu		
Panasonic	Panasonic	Intel	Panasonic		
Renesas (NEC)	Renesas (NEC)	Panasonic	Globalfoundries		
Samsung	Samsung	Renesas (NEC)	IBM		
Seiko Epson	Seiko Epson	Samsung	Intel		-
SMIC	SMIC	SMIC	Renesas (NEC)	Globalfoundries	
Sony	Sony	Sony	Samsung	Intel	
ST Microelectronics	ST Microelectronics	ST Microelectronics	SMIC	Panasonic	Globalfoundries
Texas Instruments	Texas Instruments	Texas Instruments	ST Microelectronics	Samsung	Intel
Toshiba	Toshiba	Toshiba	Toshiba	ST Microelectronics	Samsung
TSMC	TSMC	TSMC	TSMC	TSMC	ST Microelectronics
UMC	UMC	UMC	UMC	UMC	TSMC

65nm/55nm 45/40nm 22/20nm 32/28nm Market volume wall: only the largest volume products will be manufactured with the most advanced technology



130nm

90nm

# **Photolithographic Principle**



EUVL must use reflective optics

Diffraction limited resolution/ Rayleigh criterion. Smallest feature size

 $\Delta x = k\lambda/NA$ 

NA=nsinช

To achieve smaller structures: Higher NA

- Immersion
- Optimise k factors
- Double Patterning
- Multiple Patterning
- Reduce source wavelength

# **Evolution of Lithography Wavelength**



# Why 13.5 nm Lithography?



### Target Geometry (Mass-limited tin Droplet Targets)

At high repetition rates, it is not possible to use solid (slab) targets.

For EUV, rep. rate  $=10^5$  Hz





Martin Richardson et al.

Target should be fully ionized by end of laser pulse.
<sup>1</sup> Low mass Sn content. number of Sn atoms should be equal to number of radiators.



Plasma located far from nozzle. Ideally, no nozzle erosion.

## **Commercial Laser Produced Plasma Sources**



- Gigaphoton and CYMER have obtained > 250 W at Intermediate focus.
- Gigaphoton:Nd:YAG prepulse, CO<sub>2</sub> main pulse, Cymer CO<sub>2</sub> main and prepulse.
- Target should be fully ionized by end of laser pulse
- Problems: Droplet stability, CO<sub>2</sub> beam quality.

## Progress in CE



Mizoguchi Proc.2016 International Workshop on EUV Lithography http://www.euvlitho.com/2016/2016%20EUVL%20Worksho p%20Proceedings.pdf

## **Source Power Progress**



Gigaphoton: 188 W for 7 hrs (April 2016) Maximum power 264W @CE 0f 4% (In-burst mode, 27 kW CO<sub>2</sub> laser @ 100kHz)
 ~5.5% CE with ~30 μm droplet target

## **Commercial EUV Tool (ASML)**



ultra-violet-euv.html

## Water window source development



Water window : 2.34-4.38 nm.

Relative transparency of water allows investigation of biomolecules, cells and proteins in their natural aqueous environment by xray transmission microscopy or tomography





Laser plasma based full field transmission X-ray Microscope (LTXM) developed at MBI. http://www.mbiberlin.de/de/researc h/projects/4.2/BLIX/ microscope.html

# SXR Tomography: Zone Plate Optics



Stavros Lomvardas, UCSF

### Multilayer mirrors in the EUV/SXR



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## Laser produced plasmas (LPPs)



## Effect of Increasing Power Density Φ



increased kinetic losses due higher temperature. Therefore, high power density usually means tighter focus, Increased kinetic loss due to lateral expansion.

**Competition between kinetic and radiative** losses.



Harilal *et al* used a CO<sub>2</sub> pulse with  $\tau = 25 - 55$  ms Typically FWHM = 30 ns,  $\Phi = 6 \times 10^9 \text{ Wcm}^{-2}$ 

# **Energy Losses**

#### Plasma expansion:

## Fastest and most highly charged ions at centre of the plume.

(O'Connor et al. 2011, JAP 109,, 073301)



Expansion velocity increases with  $\Phi$ .

Reduce by reducing Φ or by reducing shock wave momentum (target density)

#### **Radiation:**



#### Spectrum consists of:

- lines (bound-bound transitions), in some cases lines cluster together to form a UTA (unresolved transition array)
- recombination radiation (bound-free transitions):  $I \alpha n_e^2 \langle z \rangle^4$  where  $\langle z \rangle$  is the average ionic charge
- bremsstrahlung (free-free):  $I \alpha n_e^2$ ,

Maximise line emission by reducing opacity, Maximise spectral purity by reducing recombination

Density has a 'sweet spot'

#### Most important isoelectronic sequences for line emission



Because of increase in ionization potential required to remove an electron from a closed shell, get large populations of closed shell and single electron outside closed shell species. Strongest lines from closed shell or single electron outside closed shell species. Also in LPPs spectra often dominated by these species (especially at short pulse lengths). because of high density, lines from high n states are usually not seen. Strongest lines always involve resonance transitions to the ground configuration Must allow for level rearrangement with ionization.

### Subshell ordering with increasing ionization

Ground configurations can change along isoelectronic sequences, levels reorder by principal quantum number.

- In Ca I ground configuration is (Ar) 4s<sup>2</sup>, this changes to (Ar) 3d<sup>2</sup>.
- Hyperalkali ions: PmI: 4d<sup>10</sup>5s<sup>2</sup>5p<sup>6</sup>6s<sup>2</sup>4f<sup>5</sup> changes to 4d<sup>10</sup> 4f<sup>14</sup>5s at the 15<sup>th</sup> ion stage along the sequence (*Curtis and Ellis PRL 45, 2099 1989*).
- Xe sequence: transitions based on 5p<sup>6</sup> vanish at Pr VI, ground configuration changes to {5p4f}<sup>6</sup>.

#### Reason:

The effective radial potential is of the form:

#### $-Z'e^{2}/4\pi\varepsilon_{0}r + l(l+1)h^{2}/8\pi^{2}r^{2}$

## Early studies @13.5 nm, line emission CE

APPLIED PHYSICS LETTERS 93, 091502 (2008)

## Laser wavelength dependence of extreme ultraviolet light and particle emissions from laser-produced lithium plasmas



## Two types of UTA in XUV spectra



 $4p^{6}4d^{N}-4p^{6}4d^{N-1}4f+4p^{5}4d^{N+1}$ in Sn @13.5 nm, emission from different ion stages overlap. Opacity is a major issue.  $\Delta n = 0$  transitions overlap in adjacent ion stages.

 $\Delta n > 0$  transitions do not overlap in adjacent ion stages and move to shorter wavelengths with increasing ionization....less opacity.

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#### $\Delta n = 0$ UTA: important isoelectronic sequences



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### $4p-4d \Delta n = 0 UTA$



4p<sup>n</sup>- 4p<sup>n-1</sup>4d UTA, important in lanthanides and 3<sup>rd</sup> transition row spectra.

Spin orbit split, overall, relatively weak and high energy array lies on the short wavelength side of the 5 nm UTA in W.

## **Sn UTA emission**



4p<sup>6</sup>4d<sup>N</sup>- 4p<sup>6</sup>4d<sup>N-1</sup>4f emission in Sn @13.5 nm



#### Lines due to SnXI –Sn XIV Churilov and Ryabtsev, 2006, Phys. Scr. 73 614-619

#### More recent study has shown the need to revisit and refine analysis *Windberger et al. 2016, PRA 94, 012506 Toretti et al PRA 95 042303 2017* Major problem due to spectral complexity



## Spectral shape modified by density effects: opacity, satellite lines

Sasaki et al. 2004. IEEE Journal of Quant. Electron.10, 1307

## Evolution with Z of $\Delta n=0$ , 4d-4f UTAs



### Spectral narrowing due to Configuration Interaction



#### Need to isolate the contribution from each ion stage



## EBIT (Electron Beam Ion Trap) Spectra

PHYSICAL REVIEW A 95, 042503 (2017)

#### Optical spectroscopy of complex open-4*d*-shell ions Sn<sup>7+</sup>–Sn<sup>10+</sup>

F. Torretti,<sup>1,2,\*</sup> A. Windberger,<sup>1,3</sup> A. Ryabtsev,<sup>4,5</sup> S. Dobrodey,<sup>3</sup> H. Bekker,<sup>3</sup> W. Ubachs,<sup>1,2</sup> R. Hoekstra,<sup>1,6</sup> E. V. Kahl,<sup>7</sup> J. C. Berengut,<sup>7</sup> J. R. Crespo López-Urrutia,<sup>3</sup> and O. O. Versolato<sup>1</sup>



EBIT spectra at higher electron accelerating voltages give spectra from higher ion stages, However, they are generally very weak and recorded at low resolution. Good for strongest lines.

Need for high resolution LPP or vacuum spark spectra in tandem with

low resolution EBIT data for a complete analysis.

#### **Gd EBIT Spectra**





JOURNAL OF APPLIED PHYSICS 115, 033302 (2014)

#### Tuning extreme ultraviolet emission for optimum coupling with multilayer mirrors for future lithography through control of ionic charge states

Hayato Ohashi,<sup>1,a)</sup> Takeshi Higashiguchi,<sup>1,b)</sup> Bowen Li,<sup>2</sup> Yuhei Suzuki,<sup>1</sup> Masato Kawasaki,<sup>1</sup> Tatsuhiko Kanehara,<sup>3</sup> Yuya Aida,<sup>3</sup> Shuichi Torii,<sup>4</sup> Tetsuya Makimura,<sup>4</sup> Weihua Jiang,<sup>5</sup> Padraig Dunne,<sup>2</sup> Gerry O'Sullivan,<sup>2</sup> and Nobuyuki Nakamura<sup>3</sup>

## Opacity Effects in ∆n = 0 n=4-n=4 arrays

 Spectra from metal targets dominated by continuum emission

Some strong emission and absorption lines

Large contribution from satellite lines

 Spectra of low density targets dominated by an intense Unresolved Transition Array (UTA), with greatly reduced continuum emission

Emission largely mirrors line strength distribution



### Narrowing of the UTA at reduced ion concentration

Dominant emission in all ion stages arises from  $4p^{6}4d^{N} - 4p^{6}4d^{N-1}4f + 4p^{5}4d^{N+1}$ 



# LHD spectra of Sn



### Effect of Laser Wavelength: CO<sub>2</sub> vs. Nd:YAG



1,064 nm:  $n_{ec} \approx 1 \times 10^{21} \text{ cm}^{-3}$ 10,600 nm:  $n_{ec} \approx 1 \times 10^{19} \text{ cm}^{-3}$ 



Optical depth  $\alpha$  pulse duration×(Intensity)<sup>5/9</sup>×( $\lambda$ )<sup>-4/3</sup>

Increases with pulse duration, decreases with laser wavelength.

.( Ando et al. APL **89**, 151501, 2006, Sunahara et al Plasma and Fusion Res.3,43 2008)

## Effect of prepulses with slab targets



The use of prepulses greatly enhances intensity in X-ray and EUV regimes e. g. Mochizuki et al. 1986 PRA33, 525,Kodama et al. 1987APL. 50, 720. Tanaka et al. 1988JAP . 63, 1767, Teubner et al. 1991,APL. 59,2672, Wulker et al. PRE 1994, 4920

Efficiency increases due to increased emitting volume with lower density and opacity (equivalent to using a CO<sub>2</sub> laser.) Sn output ( $\approx$ `5% bw) at 13.5 nm as a function of delay & %.



## What is Max CE?



Conversion efficiency dependence on CO<sub>2</sub> laser intensity for single (dashed) and double (solid) irradiation by a 10 ns pulse. The interpulse delay was 180 ns (*Nishihara et al Phys. Plasmas 15, 056708 2008*)



Max CE @ 60 ns delay close to wedge centre Nd:YAG, E~ 170 mJ,  $\Phi = 1.5 \times 10^{11}$  Wcm<sup>-2</sup> CO<sub>2</sub>: E~ 200 mJ,  $\Phi = 4 \times 10^9$  Wcm<sup>-2</sup> CE = 3.33±0.16% For CO<sub>2</sub> only, CE = 4.85±0.10% Allowing for overfilling of plasma by CO<sub>2</sub> CE approximately 7%

### 4d-4f UTA at shorter wavelengths: 6.x nm

Vacuum spark

Lase

nlasma

Optimum temperature for an optically thin Gd plasma ~110 eV Maximum intensity at 6.76 nm due to  $4d^{10}$   $^{1}S_{0}$ -  $4d^{9}4f$   $^{1}P_{1}$  line.

Hybrid UTA-line source



Phys. Scr. 80 (2009) 045303 (600 doi:10.1088/0031-8949/80/04/045303 EUV spectra of Gd and Tb ions excited in laser-produced and vacuum spark plasmas S S Churilov<sup>1</sup>, R R Kildiyarova, A N Ryabtsev and S V Sadovsky Establishment of the Russian Academy of Sciences Institute of Spectroscopy RAS, Troitsk, w region 142190. Russia Gd XVIII-XIX Gd Vacuum lase nlasma 50 60 70 80 90 100 110 λ.Å Tb Tb XIX & XX

The most important transitions occur in Ag-like and Pd-like: Gd XVIII-XIX, Tb XIX - XX

i.e. lons with 4d<sup>10</sup>4f and 4d<sup>10</sup> and ground states

(Sugar and Kaufman Phys. Scr. **24,** 742 (1982) and **26**, 417 (1984)

3 J in 20 ns,  $\lambda = 1.06 \ \mu m$  $\Phi = (5-8) \times 10^{11} \ W cm^{-2}$ 

an

### **CE Experiment at Gekko XII**



CE lower than Sn as higher fraction of laser energy goes into plasma heating/ionizaton

#### 4p-4d and 4d-4f arrays separate as Z increases



### Intensity Scaling of n= 4 – n=4 UTAs



Atomic number dependences of the wavelength and photon flux of the n = 4 - n = 4 ( $\Delta n = 0$ ) transitions.

#### (Shimada et al. APL 2019 Submitted)

Note that intensity falloff past Z = 70 due to decreasing HCI population is compensated for by diminishing impact of absorption due to  $4p^{6}4d^{n} \rightarrow 4p^{5}4d^{n+1}$  transitions

### ∆n = 0 4-4 UTAs in the water window region, Au, Pb and Bi (LHD Spectra)



Spectra dominated by resonant line emission to the ground state
Only Ag-, Pd- and Rh-like ions give line emission
Absorption free (Ohashi et al. JPB 48 (2015) 144011)
All require Te> 500 eV for generation

### LPP Spectrum of Pb



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### Δn = 1 UTAs; Alternative WW Source



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### $\Delta n=1$ transitions in 2<sup>nd</sup> transition row



## Integrated Intensity in the Water Window due to different UTAs



Comparison of the time-integrated emission spectra in the soft x-ray spectral region from laserproduced plasmas of Zr (a), Nb (b), Mo (c), Au (d), Pb (e), and Bi (f).



(Tamura et al. Opt. Letts.Vol. 43, No. 9, 2042)

#### **Dual Laser Illumination of Mo**



Number of photons (x 10<sup>10</sup> photons/nm•sr)

## Conclusions

- Still more CE can be attained at 13.5 nm. Modelling needs more atomic data. A definitive line classification still does not exist.
- Solid state mid-IR lasers could give better beam profiles (spatially and temporally)
- Δn=1 transitions in medium and high Z elements and Δn=0 in high Z elements can be used for water window sources.
- $\Delta n=1$  transitions require less energy for excitation than  $\Delta n=0$ . Also some match existing MLMs and atomic data needed for optimisation
- Ideal source depends on mirror bandwidth. For very narrow bandwidth at low wavelength H-like 1s-2p line in low Z ions best.
   Water/ammonia/organic liquid droplet, dual ps pulse irradiation.

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## **THANK YOU!**